

Trion Technology News

Trion Technology Introduces New Vacuum Loadlocked Plasma System For Semiconductor Production



Founded in 1989, Trion Technology Inc of Clearwater, FL, USA (www.triontech.com) supplies a variety of plasma etch and deposition equipment for the manufacturing of compound semiconductors, MEMS, and optoelectronics.

Recently, the company introduced the Titan: a compact, fully automated, vacuum loadlocked plasma system for semiconductor production. The Titan is available in either Reactive Ion Etch (RIE) configuration, High Density Inductive Coupled Plasma (HDICP) or Plasma Enhanced Chemical Vapor Deposition (PECVD) configuration. The machine is used for advanced processing of wafers from 3" to 300mm in diameter. The small system width provides very high throughput per linear foot in the fab and it is affordably priced. Trion has a fully equipped laboratory for process support both prior to and subsequent to purchase.

